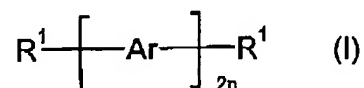


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AMENDMENTS TO THE CLAIMS

1. (Original) Process for preparing compounds of the formula (I),



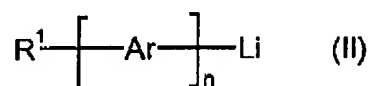
where

n is an integer from 2 to 5,

R¹ is H or a C₁-C₂₀-alkyl group optionally interrupted by one or more O or S atoms, silylene, phosphonoyl or phosphoryl groups and

Ar is substituted or unsubstituted 1,4-phenylene, 2,7-fluorene or 2,5-thiophene, with Ar being able to be identical or different,

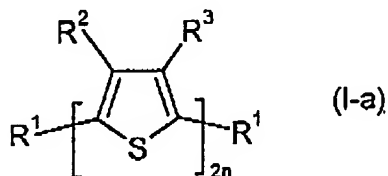
comprising completely dissolving compounds of the formula (II),



where n, R¹ and Ar are as defined for the formula (I),

in an organic solvent or solvent mixture at a temperature of from -100°C to +20°C and coupling with one another at temperatures of from -100°C to +20°C with the aid of one or more copper(II) compound(s).

2. (Original) Process for preparing compounds of the formula (I-a),



where

n is an integer from 2 to 4,

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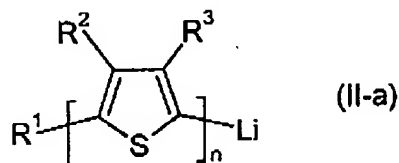
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R^1 is H or a C_1 - C_{20} -alkyl group optionally interrupted by one or more O or S atoms, silylene, phosphonoyl or phosphoryl groups and

R^2 , R^3 are each, independently of one another, H or a substituted or unsubstituted C_1 - C_{20} -alkyl group, a substituted or unsubstituted C_1 - C_{20} -alkoxy group or together form a substituted or unsubstituted C_1 - C_6 -dioxyalkylene group,

comprising completely dissolving compounds of the formula (II-a)



where n , R^1 , R^2 and R^3 are as defined for the formula (I-a),

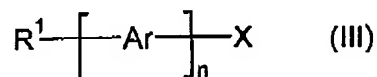
in an organic solvent or solvent mixture at a temperature of from -100°C to $+20^\circ\text{C}$ and coupling with one another at temperatures of from -100°C to $+20^\circ\text{C}$ with the aid of one or more copper(II) compound(s).

3. (Original) Process according to Claim 1, characterized in that n is 2 or 3.
4. (Original) Process according to Claim 1, characterized in that R^1 is a C_1 - C_{12} -alkyl group.
5. (Original) Process according to Claim 2, characterized in that R^2 and R^3 are each, independently of one another, H or a C_1 - C_6 -alkyl group.
6. (Original) Process according to Claim 2, characterized in that R^2 and R^3 are each H.
7. (Original) Process according to Claim 1, characterized in that alkanes, aromatics or compounds containing ether groups or mixtures of two or more of these compounds are used as solvent.

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8. (Original) Process according to Claim 1, characterized in that tetrahydrofuran or a mixture of tetrahydrofuran with alkanes is used as solvent.
9. (Original) Process according to Claim 1, characterized in that the compounds of the formula (II) are prepared by reacting compounds of the formula (III),



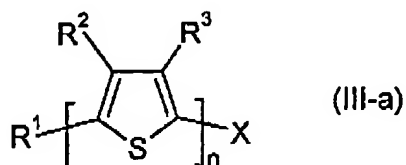
where n, R¹ and Ar are as defined in Claim 1, and
 X is H, Cl, Br or I,

with an organolithium compound at a temperature of from -100°C to +20°C in an organic solvent,

where the resulting reaction mixture is stirred further, optionally at or after heating to a temperature of from -20°C to +40°C, and is subsequently cooled back down to a temperature of from -100°C to +20°C and

the copper(II) compound is added without further work-up.

10. (Currently amended) Process according to Claim 9, characterized in that the compounds of the formula (III) are compounds of the formula (III-a),



where n, R¹, R² and R³ are as defined in Claim 1, and

wherein

n is an integer from 2 to 5,

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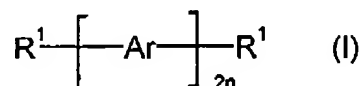
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R¹ is H or a C₁-C₂₀-alkyl group optionally interrupted by one or more O or S atoms, silylene, phosphonoyl or phosphoryl groups and

R² and R³ are each, independently of one another, H or a substituted or unsubstituted C₁-C₂₀-alkyl group, a substituted or unsubstituted C₁-C₂₀-alkoxy group or together form a substituted or unsubstituted C₁-C₆-dioxvalkylene group and

X is H, Cl, Br or I.

11. (Original) Process according to Claim 9, characterized in that the organolithium compound is a lithium amide, or a complexed or uncomplexed alkyllithium compound.
12. (Original) Process according to Claim 1, characterized in that the copper(II) compound is a copper(II) halide, a copper(II) salt of a carboxylic acid or sulphonic acid, or a copper(II) alkoxide.
13. (Original) Process according to Claim 1, characterized in that the reaction mixture is stirred further at temperatures of from -80°C to +40°C to complete the coupling reaction.
14. (Currently amended) A semiconductor layer ~~Layers~~ comprising compounds of the formula (I)



~~where n, R¹ and Ar are as defined in Claim 1 to 4,~~

wherein

n is an integer from 2 to 5,

R¹ is H or a C₁-C₂₀-alkyl group optionally interrupted by one or more O or S atoms, silylene, phosphonoyl or phosphoryl groups and

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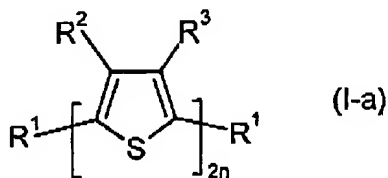
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Ar is substituted or unsubstituted 1,4-phenylene, 2,7-fluorene or 2,5-thiophene, with
Ar being able to be identical or different.

~~characterized in that they contain~~ wherein the layer contains 0.5% by weight or less of
 chlorine ~~and are semiconductive.~~

15. (Currently amended) The layer ~~Layers~~ according to Claim 14, characterized in that they
 contain 0.3% by weight or less of chlorine.

16. (Currently amended) The layer ~~Layers~~ according to Claim 14, characterized in that the
 compounds of the formula (I) are compounds of the formula (I-a),



~~where n, R¹, R² and R³ are as defined in Claim 1~~
wherein

n is an integer from 2 to 5,

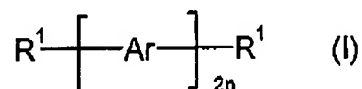
R¹ is H or a C₁-C₂₀-alkyl group optionally interrupted by one or more O or S atoms,
silylene, phosphonoyl or phosphoryl groups and

R² and R³ are each, independently of one another, H or a substituted or unsubstituted
C₁-C₂₀-alkyl group, a substituted or unsubstituted C₁-C₂₀-alkoxy group or together
form a substituted or unsubstituted C₁-C₆-dioxyalkylene group.

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17. (Currently amended) A process for preparing active and light-emitting electronic components comprising incorporating layers ~~the layer~~ according to Claim 14 as semiconductors.
18. (Currently amended) ~~Process for producing the layers~~ A process for producing the layer as claimed in Claim 14, which comprises applying a compound characterized in that compounds of the formula (I),



~~where n, R¹ and Ar are as defined in Claim 1,~~

wherein

n is an integer from 2 to 5,

R¹ is H or a C₁-C₂₀-alkyl group optionally interrupted by one or more O or S atoms, silylene, phosphonoyl or phosphoryl groups and

Ar is substituted or unsubstituted 1,4-phenylene, 2,7-fluorene or 2,5-thiophene, with Ar being able to be identical or different,

~~are applied~~ from solution or from the gas phase to a suitable substrate.

19. (Original) Process according to Claim 18, characterized in that the compounds of the formula (I) are applied from the gas phase.
20. cancelled